



PATENT
8733.378.00

2812
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Myoung-Su YANG

Group Art Unit: 2812

Application No.: 09/748,871

Examiner: R. E. Pompey

Filing Date: December 28, 2000

For: METHOD OF FORMING A POLYCRYSTALLINE SILICON LAYER

Sir:

AMENDMENT TRANSMITTAL

Transmitted herewith is an amendment

<input type="checkbox"/>	No additional fee is required
<input type="checkbox"/>	Small entity status of this application under 37 C.F.R. §1.9 and §1.27 has been established by a verified statement previously submitted.
<input type="checkbox"/>	Small entity status of this application under 37 C.F.R. §1.9 and §1.27 has been established by a verified statement submitted herewith.
<input type="checkbox"/>	Additional documents filed herewith:

The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS	RATE	CALCULATIONS
TOTAL	19	MINUS	20	0	X \$18	= \$0.00
INDEPENDENT	5	MINUS	3	2	X \$84	= \$168.00
		<input type="checkbox"/>	MULTIPLE DEPENDENT CLAIMS		+ \$280	= \$0.00
			TOTAL OF ABOVE CALCULATIONS			\$168.00
		<input type="checkbox"/>	Reduction by 50% for filing by Small Entity			\$0.00
		<input type="checkbox"/>	Recordation of Assignment		+ \$40	\$0.00
			TOTAL			\$168.00

<input type="checkbox"/>	A check in the amount of \$168.00 is attached for the fees.
<input checked="" type="checkbox"/>	Please charge any additional Fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit Account No. 50-0911. A copy of this sheet is enclosed.
<input checked="" type="checkbox"/>	If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 50-0911. A copy of this sheet is enclosed.

1900 K Street, N.W.
Washington, D.C. 20006
Telephone No.: (202) 496-7500
Facsimile No.: (202) 496-7756

Date: January 6, 2003

Respectfully submitted,

MCKENNA LONG & ALDRIDGE LLP

By Teresa M. Arroyo
Teresa M. Arroyo
Registration No. 50,015



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PATENT TRADEMARK OFFICE

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13/13

Application No.: 09/748,871
Art Unit: 2812

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Examiner: POMPEY, RON EVERETT

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POLYCRYSTALLINE SILICON LAYER

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AMENDMENT

Commissioner for Patents
Washington, DC 20231

Dear Sir:

In response to the Examiner's Non-Final Office Action dated October 7, 2002, the following amendments and remarks are respectfully submitted.

IN THE SPECIFICATION

Please **AMEND** the specification as follows (A marked up version of the amended specification is attached):

Page 3, Paragraph beginning at line 12 of the substitute specification filed February 23, 2001:

FIGS. 1A to 1C are plan views illustrating a crystallization process of a polycrystalline silicon layer. The distance between adjacent silicon seeds 11 is less than the maximum grain growth distance. It is desirable that the silicon seeds 11 are uniformly distributed. The silicon grains 13 grow laterally, centering on the silicon seed 11, and